

Notice of References CitedApplication/Control No.
09/633,857Applicant(s)/Patent Under
Reexamination
AHLGREN ET AL.Examiner
Robert M KunemundArt Unit
1765

Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,288,645	02-1994	Toshima et al	436/144
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Maley et al., "Infrared reflectance spectroscopy of very thin films of hydrogenated amorphous silicon", J. Non-crystalline Solids., vol 114 (1) 1989 pages 163-5 abstract only.
	V	Abelson et al., "Surface hydrogen release during the growth of a-Si:H by reactive magnetron sputtering", Journal of Vacuum Science and Technology A vol. 8 no.3 pt. 1 pages 1364-8 May-June 1990 abstract only.
	W	Pejnefors et al. "Chemical vapor deposition of undoped and in-situ boron and arsenic doped epitaxial and polycrystalline silicon films grown using silane at reduced pressure", Journal of Applied Physics vol. 88 no. 3 pages 1655-63 August 2000
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.